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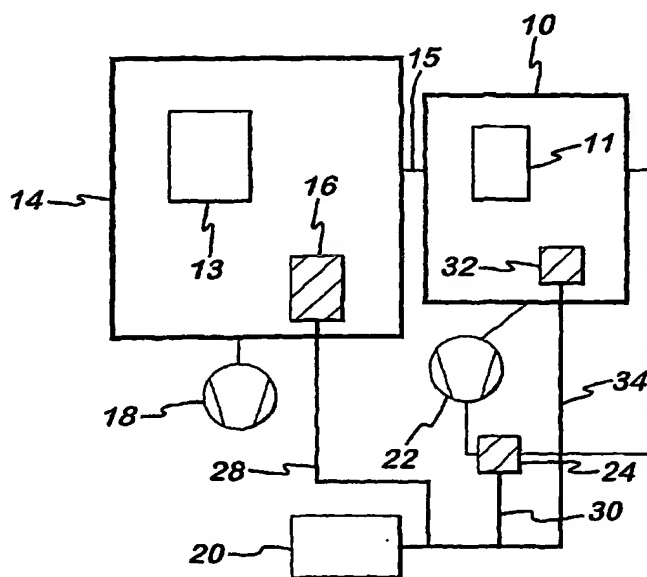
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(54) Title: LITHOGRAPHY APPARATUS WITH EXTREME ULTRAVIOLET LIGHT SOURCE



(57) Abstract: Lithography apparatus comprises a lithography tool (13) housed in a first chamber (14), and a source of radiation (11) at or below ultra violet wavelengths housed in a second chamber (10) connected to the first chamber (14) to enable radiation generated by the source to be supplied to the tool. A cryogenic vacuum pump (16) is provided for at least one, preferably for each, of the chambers (10, 14). A target material, such as xenon, supplied to the source for the generation of radiation is pumped from the second chamber (10), cryogenically purified and re-supplied to the source (11). A cryogenic refrigerator (20) supplies cryogen to the cryogenic purifier (24) and to the cryogenic vacuum pump(s) (16).

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